CHARACTERIZATION OF Li_xMo_{0.13}Mn_{1.87}O₄ THIN FILMS FOR MICROBATTERIES

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In other to improve the electrochemical properties of spinel $LiMn_2O_4$ electrode, many transition metals have been introduced for substitution[1]. In our works, the spinel $LiMn_2O_4$ was deposited by sputtering and Mn ion was substituted for Mo by co-sputtering of MoO₂-pellet.

LiMn₂O₄ thin films were deposited by using radio frequency magnetron sputtering with 2-inch diameter of $LiMn_2O_4$ target (99.97% purity). The chamber was evacuated to 5.0 x 10^{-6} Torr as a base pressure and working pressure was maintained to 10 mTorr with a forming gas of Ar and O₂. RF power used during a process was 1.5 W/cm². B-doped p-type Si (111) wafers were used as substrate on which Pt was deposited in thickness of 200 nm as a current collector by D.C. sputtering. To substitute cobalt ion, 1 cm-diameter MoO₂ pellets were placed on the $LiMn_2O_4$ target during sputtering. Deposited films were annealed using a horizontal tube furnace. Compositions of films were analyzed by ICP and RBS. Surface roughness of the film before and after the heat treatment was measured by AFM. Surface morphologies of the films were obtained by FE-SEM. For electrochemical analysis, half-cells were made with the annealed thin films as a cathode, the lithium metal as an anode, and 1 M solution of LiPF₆ in EC-DMC(1:1) as an electrolyte.

A composition of the Mo-doped films was $LiMn_{0.13}Mn_{1.87}O_4$. As shown in Fig.1, $LiMn_2O_4$ and $LiMn_{0.13}Mn_{1.87}O_4$ had almost same structure. Those Films had a (111) preferred orientation and a small quantity of impurity phase such as Li_2MnO_3 . We conclude that no structural change occurred by substitution. Figure 2 showed the result of AFM measurement. Mo-doped film was rougher than the $LiMn_2O_4$ (Fig, 2). The higher value of roughness promised improved performance due to higher area of electrode/electrolyte interface, which was introduced the reaction area of intercalation reaction. As shown in Fig. 3, in spite of wide windows, the cycleability of the $LiMn_{0.13}Mn_{1.87}O_4$ film was better than that of the $LiMn_2O_4$.

The results of XRD, FE-SEM and TEM of the cycled films will be discussed at the meeting.

AKNOWLEADGEMENTS

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REFERENCES

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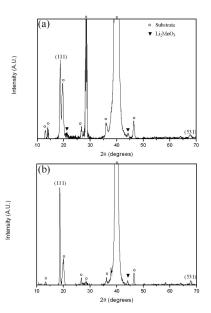
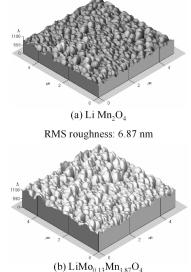
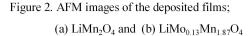


Figure 1. XRD patterns of the deposited films; (a) LiMn₂O₄ and (b) LiMo_{0.13}Mn_{1.87}O₄



RMS roughness: 10.4 nm



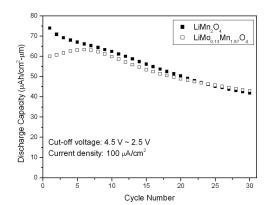


Figure 3. Discharge capacities of the deposited films.